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			Application Number	10/816	5,179					
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]	FORM		First Named Inventor	Chung						
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(to be used to	all correspondence after initial t	ilina)	Examiner Name							
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Firm Name	SIGNA	UKE C	OF APPLICANT, ATTOR	KNEY, C	JK AGEN I					
	Alleman Hall McCoy	Russell	& Tuttle LLP							
Signature	M. Matt	Luis	the							
Printed name	M. Matthews Hall		<del>- ,</del>							
Date	January 26, 2005		R	Reg. No.	43,653					
	nat this correspondence is be e as first class mail in an env	eing facsir		O or depos	ILING sited with the United States Postal Service with P.O. Box 1450, Alexandria, VA 22313-1450 on					
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This collection of information is required by 37 CFR 1.5. The information is required to obtain or retain a benefit by the public which is to file (and by the USPTO to process) an application. Confidentiality is governed by 35 U.S.C. 122 and 37 CFR 1.11 and 1.14. This collection is estimated to 2 hours to complete, including gathering, preparing, and submitting the completed application form to the USPTO. Time will vary depending upon the individual case. Any comments on the amount of time you require to complete this form and/or suggestions for reducing this burden, should be sent to the Chief Information Officer, U.S. Patent and Trademark Office, U.S. Department of Commerce, P.O. Box 1450, Alexandria, VA 22313-1450. DO NOT SEND FEES OR COMPLETED FORMS TO THIS ADDRESS. SEND TO: Commissioner for Patents, P.O. Box 1450, Alexandria, VA 22313-1450.



In re Application of:

Date: January 26, 2005

CHUNG J. LEE, ATUL KUMAR, CHIEH CHEN and YURI PIKOVSKY

Serial No.

10/816,179

Group Art Unit 1763

Filed

March 31, 2004

For

SYSTEM FOR FORMING COMPOSITE

POLYMER DIELECTRIC FILM

Mail Stop AMENDMENT Commissioner for Patents P.O. Box 1450 Alexandria, Virginia 22313-1450

Sir:

## SUPPLEMENTAL INFORMATION DISCLOSURE STATEMENT UNDER 37 C.F.R. §§ 1.56, 1.97, and 1.98

Applicants are submitting this Supplemental Information Disclosure Statement pursuant to 37 C.F.R. §§ 1.56, 1.97, and 1.98 to disclose to the U.S. Patent and Trademark Office the patents, publications, applications, and/or other references listed on the enclosed, completed PTO-1449 form(s). The filing of this Supplemental Information Disclosure Statement should not be construed as a representation that a search has been made or as an admission that the listed references are prior art for this application. Applicants respectfully request that the listed references be expressly considered during prosecution of the application, and that the references be made of record therein and appear among the "references cited" on any patents issuing therefrom.

## **CONTENT OF DISCLOSURE**

This Supplemental Information Disclosure Statement includes (1) six pages of PTO-1449 forms, and (2) a legible copy of each foreign and non-patent reference, if any, listed on the form(s). However, because this application was filed on or after July 1, 2003, no copies of U.S. patents or published U.S. patent applications are included.

## TIMING OF DISCLOSURE / FEE INFORMATION

This Supplemental Information Disclosure Statement is being filed, to the best of the undersigned's knowledge, either (1) before the mailing of a first Office action on the merits, or (2) before the mailing of a first Office action after the filing of a request for continued examination under 37 C.F.R. § 1.114. Therefore, in accordance with 37 C.F.R. § 1.97(b), no fee or statement under 37 C.F.R. § 1.97(e) is required.

Please contact the undersigned with any questions or comments regarding this Supplemental Information Disclosure Statement.

## **CERTIFICATE OF MAILING**

I hereby certify that this correspondence is being deposited with the United States Postal Service as first class mail in an envelope addressed to: Mail Stop AMENDMENT, Commissioner for Patents, P.O. Box 1450, Alexandria, Virginia 22313-1450, on January 26, 2005.

Respectfully submitted,

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Attorney for Assignee

FORM PTO-1449 DOCKET NUMBER APPLICATION NUMBER JAN 2 8 2005 **DSI 302** 10/815,994 INFORMATION DISCLOS **APPLICANTS** CITATION IN À Chung J. Lee et al. FILING DATE **GROUP ART UNIT** March 31, 2004 2827 **U.S. PATENT DOCUMENTS** EXAMINER DOCUMENT CLASS DATE NAME SUB FIL. DATE INITIAL NUMBER **CLASS** IF APPROP. 3,268,599 08/23/1966 Chow 3,274,267 09/20/1966 Chow 3,280,202 10/18/1966 Gilch 3,288,728 11/29/1966 Gorham 3,332,891 07/25/1967 Chow et al. 3,342,754 09/19/1967 Gorham et al. 3,349,045 10/24/1967 Gilch 3,379,803 04/23/1968 Tittmann et al. 3,503,903 03/31/1970 Shaw et al. FOREIGN PATENT DOCUMENTS DOCUMENT DATE COUNTRY CLASS TRANSLATION SUB NUMBER CLASS YES NO EP 0 349 032 A2 **EPO** 01/03/1990 EP 0 523 479 A2 01/20/1993 **EPO** EP 0 856 503 A1 08/05/1998 **EPO** OTHER DOCUMENTS Chow et al., Poly (a,a,a',a'-tetrafluoro-p-xylylene), Journal of Applied Polymer Science, Vol. 13, No. 9, pp. 2325-2332, 1969. Chow et al., The Synthesis of 1,1,2,2,9,9,10,10-octafluorou2, 2Paracyclophane, Journal of Organic Chemistry, Vol. 35, No. 1, pp. 20-22, 1970. Iwamoto et al., Crystal Structure of Poly-p-xylylene. I. The a Form, Jour. Polymer. Sci. Polymer. Phys. Ed., Vol. 11, pp. 2403-2411, 1973. DATE CONSIDERED **EXAMINER** 

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